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				4717-6100		10/664781	
				APPLICANT:			
				Christophe MALEVILLE et al.			
				FILING DATE:		GROUP:	
				9/16/2003		1746	
<b>U.S. PATENT DOCUMENTS</b>							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
hsc	AA 5,158,100	10/1992	Tanaka et al.	134	105		
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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
hsc	AI EP 0 476 897 A2	3/1992	Europe			X	
hsc	AJ EP 0 731 495 A2		Europe			X	
	AK						
<b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
hsc	AL	Kaneko et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (II)- in situ UVOC", Journal of Applied Physics, Vol. 28, No. 12, pp. 2425-2429 (1989)					
	AM						
	AN						
	AO						
EXAMINER				DATE CONSIDERED			
S. C. Lee				8/11/04			
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